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6. (Amended Herein) The over-coating composition according to Claim 1, wherein said basic compound is selected from the group consisting of an amine compound and a hydroxy salt thereof; an amide compound; a urethane compound; and a mixture thereof.

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9. (Amended Herein) The over-coating composition according to claim 6, wherein said amine compound is selected from the group consisting of L-proline, a tetraalkylammonium hydroxide salt, a tri(hydroxyalkyl)amine, and a mixture thereof.

10. (Amended Herein) The over-coating composition according to claim 9, wherein said tetraalkylammonium hydroxide salt is selected from the group consisting of tetramethylammonium hydroxide and tetramethylammonium hydroxide pentahydrate.

11. (Amended Herein) The over-coating composition according to claim 9, wherein said tri(hydroxyalkyl)amine is triethanolamine.

Please add new Claim 21 as follows:

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21. (New) A method for producing a substantially vertical photoresist pattern during a photolithography process, said method comprising coating an over-coating composition of Claim 1 to a substrate on top of a photoresist composition layer prior to subjecting the substrate to a photolithography process.

REMARKS

Claims 1-20 are pending in this application. Claims 14-20 are withdrawn from consideration by the Examiner. Claims 1, 6, 9-11, and 15 have been amended. Support for such amendments can be found throughout the specification. For example, support for amending Claim 1 can be found on page 4, lines 23-30. New Claim 21 has been added. Upon entry of this Amendment, Claims 1-21 will be pending in this